Ballistic Magnetoresitance over 4000% in Ni-Ni Electrodeposited Nanocontacts

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This paper reports ballistic magnetoresistance values over 4000% measured in electrodeposited Ni-Ni nanocontacts with T geometry previously developed . Over the time, after several magnetic field cycles, the ballistic magnetoresistance relaxed to a 400%. While that the magnetoreistance of a contact could rise indefinitely; relaxtion and reproducibility are, however, the main issue. We find that the tip ending radius conforming the contacts appears not to play the main role.

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Ballistic magnetoresitance (BMR) of 300% was first reported by Garcia, Muñoz and Zhao, in atomic contacts of resistances larger than 1000 Ω [1] and was explained as resulting from scattering with very sharp magnetic domain walls [2,3]. Later on it was possible to obtain, by electrodeposition techniques, contacts of a few Ohms resistance with a T shape configuration (see Fig.1) having BMR of 700% [4], that relax to a final ´equilibrium´value of 400% after field cycling the sample during a few days. Contrary to the case of atomic size contacts, the magnetoresistance of these few Ohms contacts (10-30 nm size) cannot be attributed [5] to domain wall scattering [2,3]. This has been reported by us in Ref. 4. We postulated that the physical cause of BMR in the large nanocontacts was the presence of a dead magnetic layer at the contact point. Thus if the polarization at the Fermi level could be modified to a value near unity, then the resulting BMR could rise up to infinity.

Recently BMR values over 3000% in a Ni-Ni nanocontact with T geometry have been reported [6]. The large increase of BMR over the values previously obtained by Garcia *etal*. [4] in similar contacts (3150% against 700%) was attributed to the fact that the tip ending had been sharpened to 40 nm by electrochemical etching in KCl [6] (see Fig.1).

In this communication, we report Ni-Ni contacts made by electrodeposition with the same T shape configuration that have 4000% BMR. Both the tip I and the wire II (Fig. 1) are treated electrochemically with KCl, but the tip end was 1000 nm in size, and not 40 nm size as in the experiment above [6], which implies that the increase of BMR is not due to the tip size but depends, instead, on the electrochemical processing.

We arranged the Ni wires in a T configuration as shown in Fig.1. The applied field during magnetoresistance measurements is in the direction of the Ni wire labeled ´I´in Fig.1. This arrangement, originally conceived by us, is well suited for magnetoresistance across the Ni nanocontact. The tip of the wire ´I´in Fig.1 was positioned to within a few microns to few tens of microns to the Ni wire labeled ´II´prior to electro-deposition of the Ni nanocontact. The Ni wires (except for the region in the immediate vicinity of the contact) were insulated by a fast curing resin epoxy in order to limit the deposition to the gap between the wires. The resin epoxy also firmly holds the Ni wires to the underlying dielectric substrate. The

Ni nanocontacts were electrochemically deposited at room temperature. Electro-deposition was performed from a saturated nickel sulphate (Ni_2SO_4) electrolyte (PH=3.5). We used a cathode potential of -1.2 V against a saturated calomel electrode. Deposition times were typically less than one minute. The magnetoresistance measurements were performed at room temperature for magnetic fields up to H=3000 Oe in the current-in-plane / field-in-plane(CIP/FIP) confiuration. The process of fabrication of the tip ´I´was as follows: we first made a tip by breaking mechanically a Ni wire of diameter (0.125 mm). Then we used an electrochemical etching technique to get the tip radius down to 600-1000 nm. The Ni wire was deeped into a cell filled with 2M KCl and a 2V constant voltage was applied. The tip is shown in Fig.1a. Etching takes place according to the anodic reaction $Ni(s) + 2Cl^- = NiCl_2 + 2e^-$; the reaction occurring at the Platium cathode is $2H_2O + 2e^- = H_2 + 2OH^-$. It should be stressed that electrochemical sharpening of the tip was not performed, contrarily to the case in Ref. 6. It would appear that sharpening the tip to 40 nm is not the determining step for obtaining contacts with high BMR values, as stated in Ref. 6. We show here that one can get 4000% BMR with a tip sharpened to 1000 nm diameter. Instead, we believe that the additional electrochemical treatment in the KCl cell is the cause for the high BMR.

Fig.2 shows consecutive magnetoresistance loops in a sample whose initial zero-field contact resistance was 15 Ω after electro-deposition. This contact resistance R determines the diameter d=$\sqrt{1000/R(\Omega)}$ (in nm) [4] of the nanocontact, being equal to 8 nm for this sample. As seen in Fig. 2a, the resistance increases rapidly with increasing the field strength. At saturation the resistance rises to 634 Ω, after which it remains essentially unchanged with further increases in field strength. This represents a 4000% BMR at room temperature in a field about 800 Oe. The peak of the BMR curve corresponds to about 280 Oe. Fig. 2b shows the BMR curve of the same sample measured after several hours. It can be seen that, although the low field resistance increases somewhat and the BMR value decreases significantly, the high field saturation resistance remains virtually unchanged. This relaxation process needs to be understood and is very important, cannot be neglected, as was already stressed in our previous work [4,7] .

In conclusion we have reported BMR over 4000% and have shown that the size of the tip conforming the contact does not play a relevant role because tips 1 micrometer size, as reported here, give also BMR values much larger than the ones previously reported in [6] . In fact, there is not a single insight in the physics of the BMR process that would point to the importance of sharpening the tip to achieve very high BMR values. The whole thing is regulated by the nanocontacts and on the products O, S, Cl, etc, or density of states at Fermi, that can be segregated at the contact. This has been reported in a very recent paper (cond-mat/0207323) [8] indicating that the localization, through bonds, of the Ni sp-electrons can lead to full polarization of d-electrons contributing to current and therefore to an indefinitely grow of the BMR.Notice that [2,3]:

$$\mathrm{BMR}(\%) = \mathrm{D}\times 2\mathrm{P}^2/(1-\mathrm{P}^2)\times 100 \qquad (1)$$

Where D is the dynamical factor approximately equal to unity for very thin domain wall [2,3] fixed by the dead magnetic layer. This is the factor that gives the spin conservation in the current or nonadiabaticity. P is the polarization of the electrons contributing to the current if the sp electrons in the case at hand of Ni are bonded by Cl this will not contribute to the current and only the fully polarized d-electrons will participate to the current and thus P˜1. Inserting these values in equ. 1 it can be seen that BMR can grow indefinitely (see Ref. 9).

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[8] N. Garcia, What is the Physical Explanation for the Very Large Ballistic Magnetoresitance Observed in Electrodeposited Nanocontacts?. cond-mat/0207323.

[9] Regarding the indefinitely grow of BMR N.García reports that in the year 2000 his students Y.W. Zhao and M. Muñoz wrote a report to him were BMR values up 100000% were observed in three cases as well as other over 1000% in 10-30nm section nanocontacts. These data were discarded because we did not understand them and could not be justified for Ni using ref [2,3]. In the view of the dead magnetic layer and presence of other chemical agents that Ni in the dead layer interpretation, these row data as well as many other, the most representative out of over 10000 samples, will be presented in a Review-Report shortly

FigureCaptions :

Fig.1 (a) Optical microscope view of the tip conforming the T contact in 1(b). The tip and the wire have been given an electrochemical treatment in KCl (see text). This seems to enhance BMR to very large values, irrespective of tip ending dimensions.

Fig.2 (a) BMR cycles showing values up to 4014%. However, a new cycle was done after a time and the BMR was reduced to 354% (see 2(b)). This happens always to our samples and is the important point to understand [4,7].

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